



Ultrapure Fluid Handling and Wafer Cleaning Conference 2008

Santa Clara Convention Center, Santa Clara, CA
February 13, 2008
8:00am – 3:00pm

PROGRAM OUTLINE

Time	Session
8:00 am	Reception and Registration - Breakfast provided by Levitronix
8:30 am	<u>Welcoming remarks</u> Reto Schoeb, Levitronix
8:40 am	<u>Ultra Pure Water Immersion Lithography: Purification Needs and Solutions</u> Gregg Conner, Entegris, Inc.
9:05 am	<u>Process to drain and reclaim – A highly flexible chemical dispense system for SEZ single wafer wet cleaning tools.</u> Bernhard Loidl, SEZ Inc.
9:30am	<u>Material and component selection and evaluation for ultrapure water and process chemical systems in the semiconductor industry</u> Jens Tschmelak, M+W Zander
9:55 am	<u>Evaluation of Particle Shedding and Trace Metal Extraction from High Purity Pumps</u> Mark R. Litchy, CT Associates, Inc.
10:20 am	Break provided by Levitronix
10:30 am	<u>Meeting Selectivity Needs with Unique Corrosion Inhibitors in Cleaning and Surface Finishing Practices</u> John Moore, DAETEC, LLC
10:55 am	<u>The effect of exposure conditions on component life in HCl solutions</u> Don Grant, CT Associates, Inc.
11:20 am	<u>Developing a method to match in-situ metrology to chemical concentration requirements</u> Charlie Peterson, Edwards Ltd.
11:45 pm	Lunch provided by Levitronix
12:45pm	<u>Single-Wafer Marangoni Drying for Advanced Technology Node Cleaning Applications</u> James (Jim) Papanu, Ph.D.
1:10 pm	<u>Quantitative measurements of pattern damage and particle removal forces for below 45 nm wafer cleaning</u> Jin-Goo Park, Div. of Materials and Chemical Engineering Hanyang University, Korea
1:35 pm	<u>Monitoring Nanoparticles in Liquid Systems</u> Ross Bryant, Particle Measuring Systems Inc.
2:00 pm	<u>Investigation of additives on the corrosion and cleaning efficiency of post CMP cleans</u> Robert Donis, Air Liquide
2:25pm	Q&A and distribution of REGISTRATION GIFT
3:00 pm	Adjourn